



# Static Photon Emission

## Background

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# Photon Emission: Fundamentals

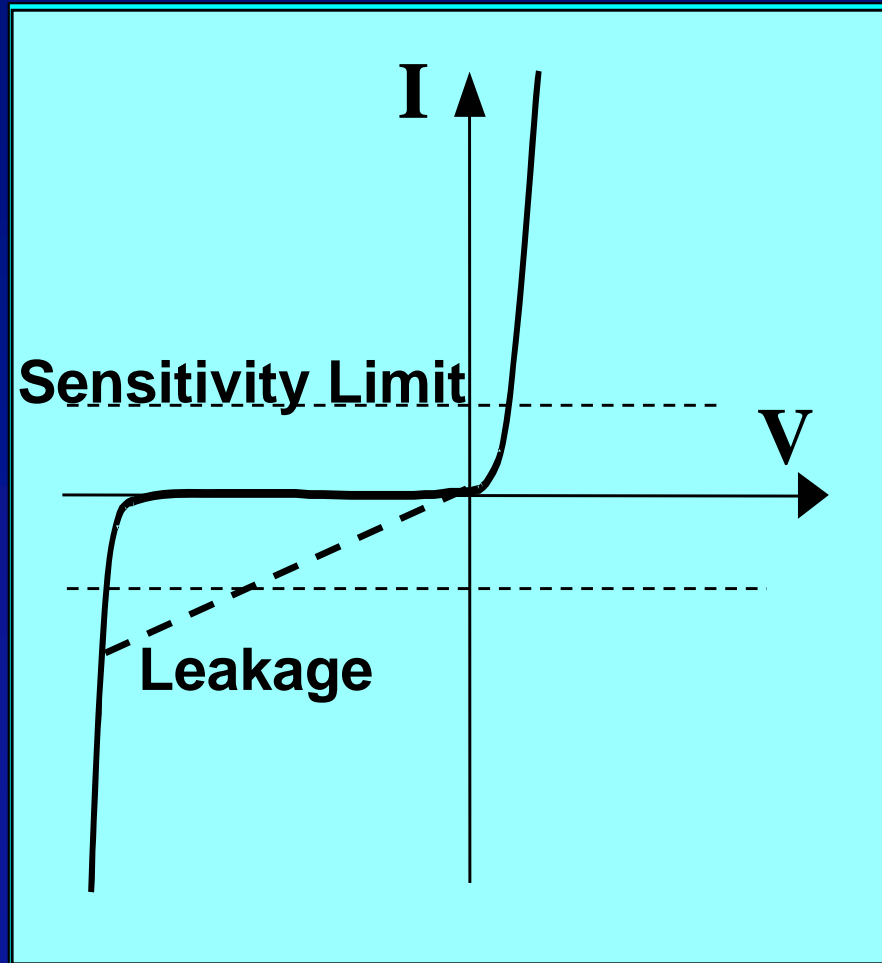
## The two Basic Mechanisms of Photon Emission in Si

**Example:  
P/N Junction:**

**Reverse Bias**

**1) Intraband:**

Carriers pick up kinetic energy in E-field and relax by emitting photons

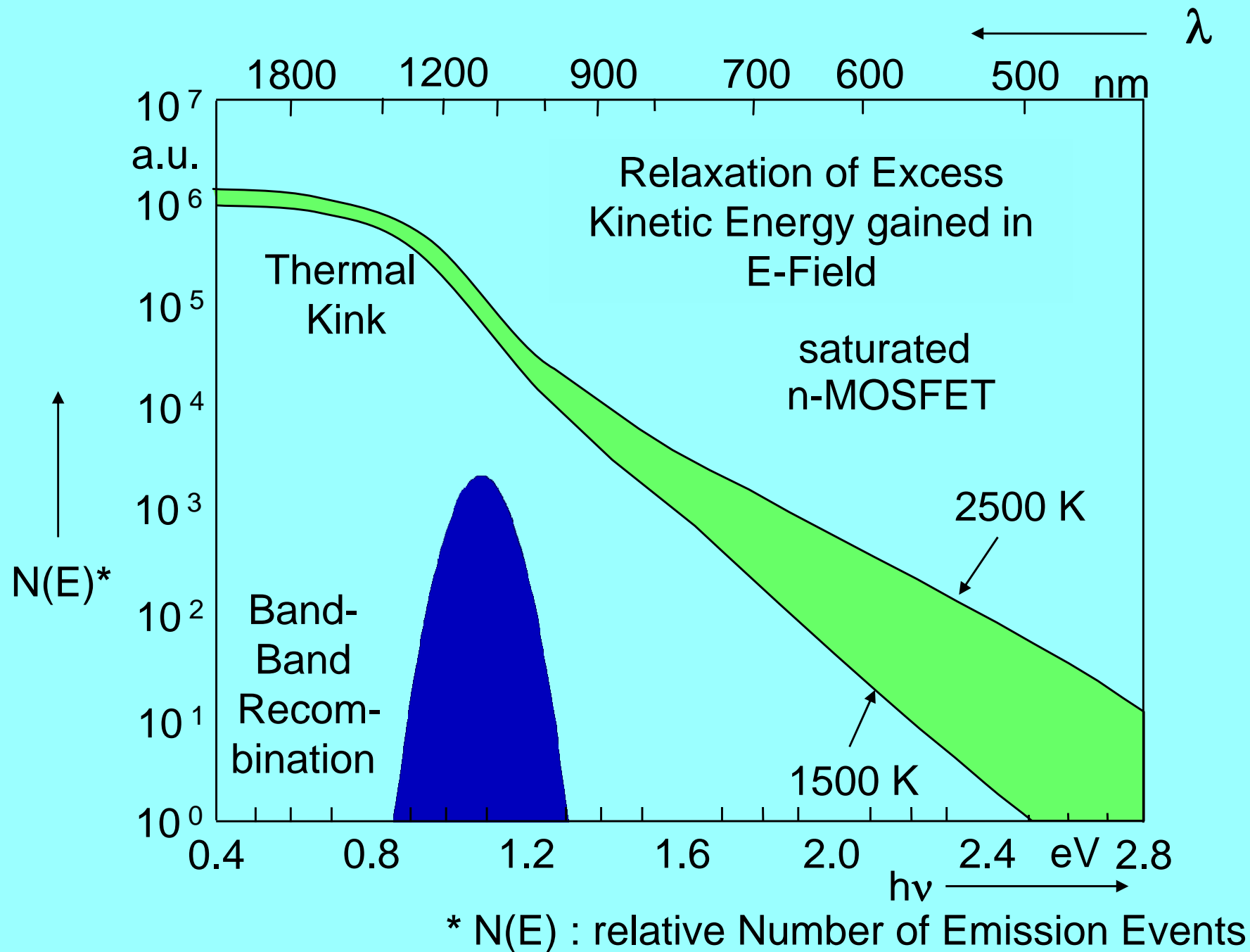


**Forward Bias**

**2) Interband:**

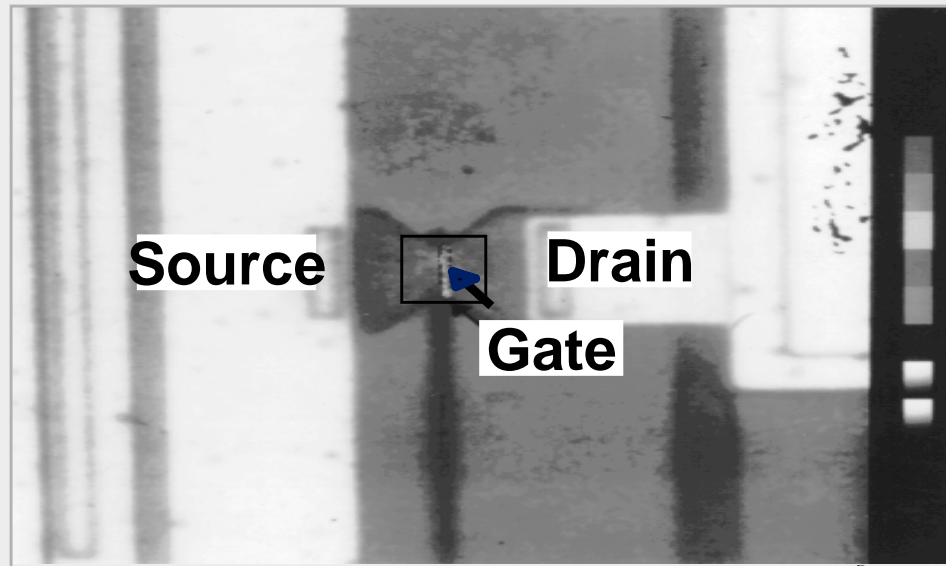
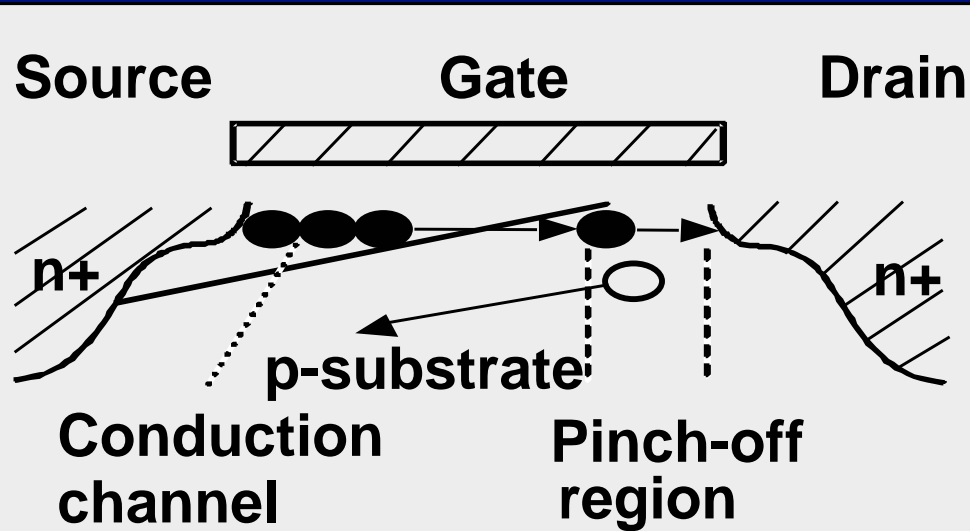
Band-band recombination of injected excess carriers

# Photon Emission Fundamentals: Spectra



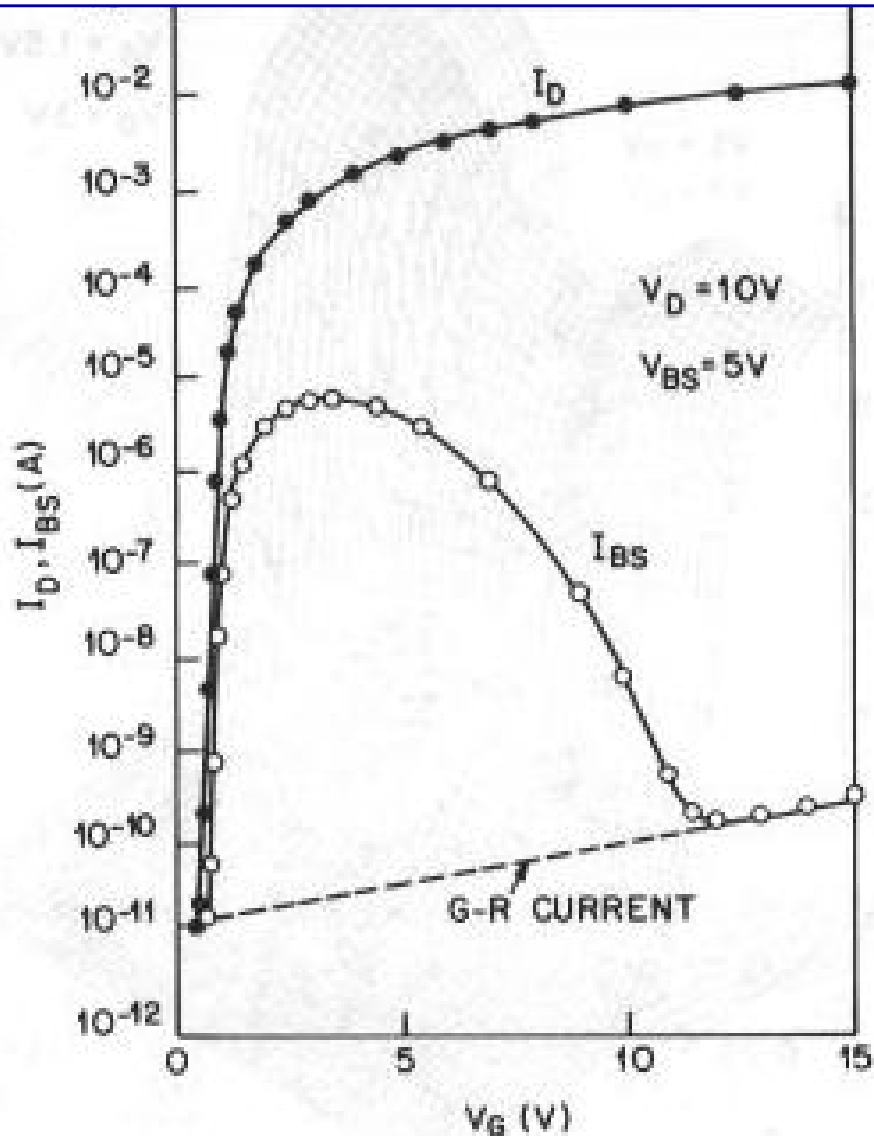
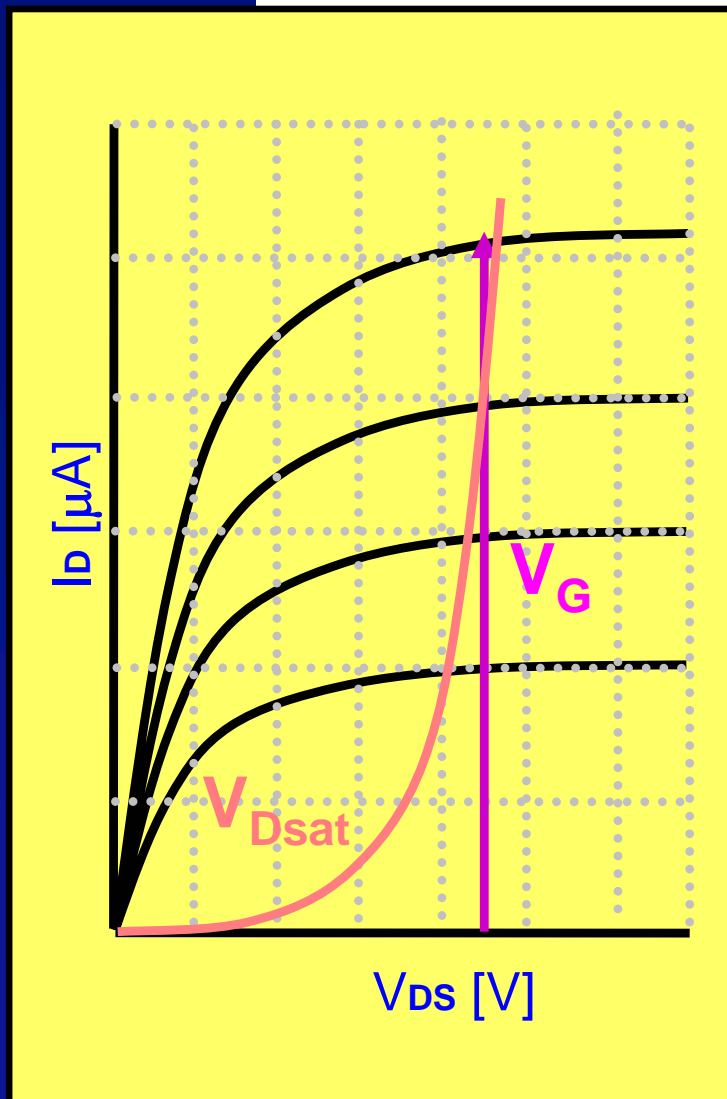
# Photon Emission from MOS FET

Saturation



$W/L = 10$   $w = 1\mu\text{m}$   
 $V_D = 6\text{V}$ ,  $V_G = 3\text{V}$

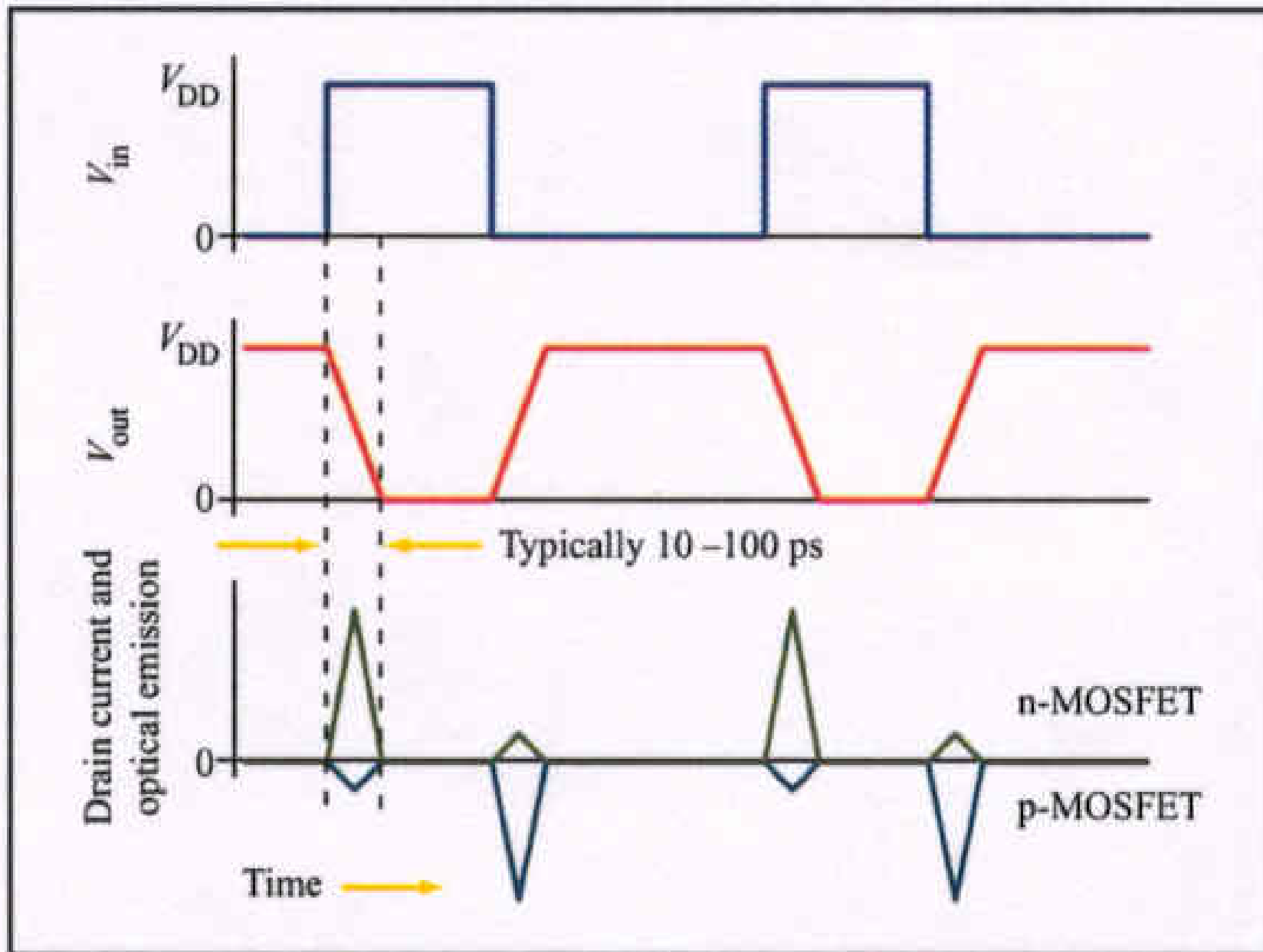
# MOS: Saturation and Substrate Current



Sze, Semiconductor  
Devices

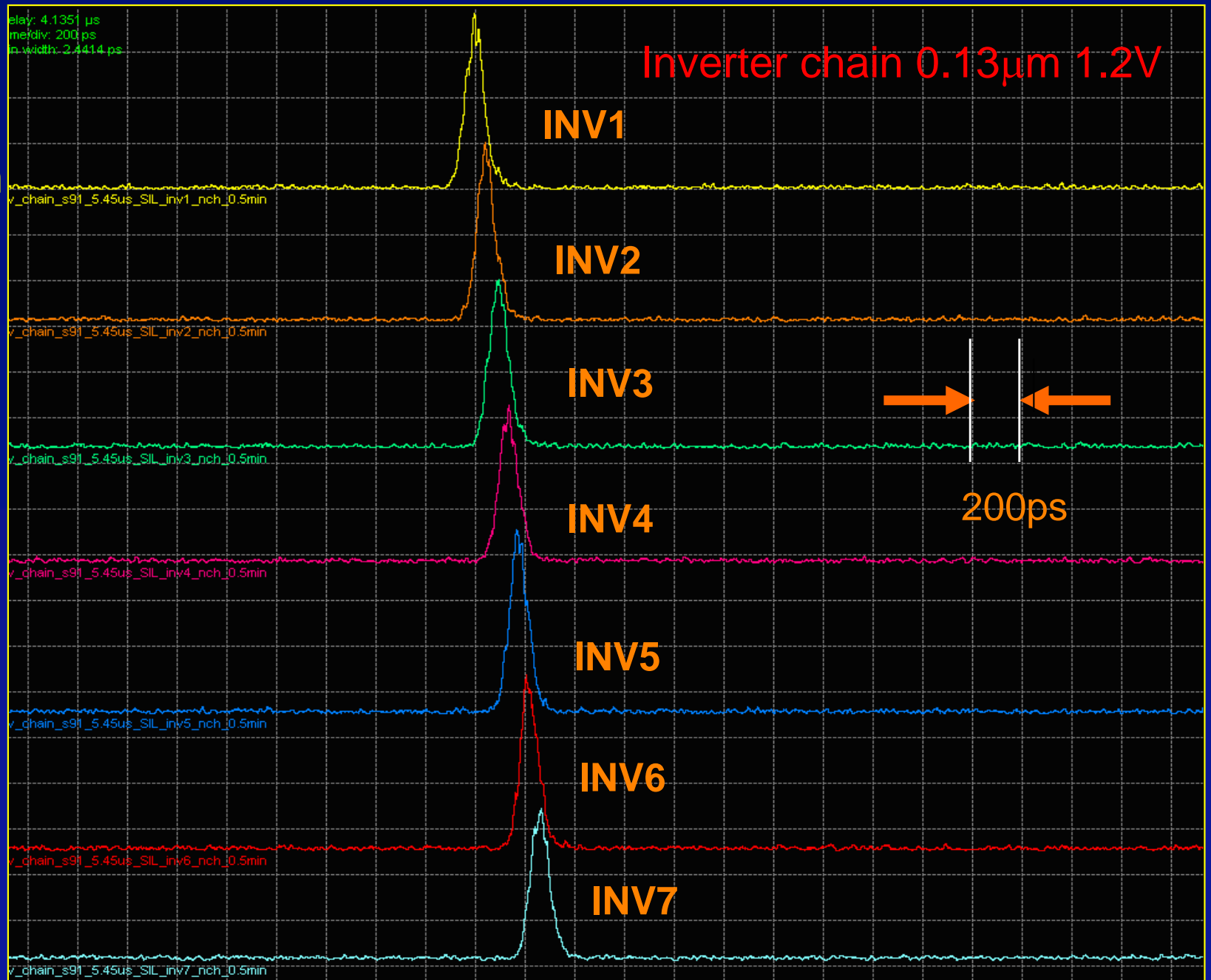
Fig. 46 Drain current and substrate current versus gate voltage of a long-channel MOSFET. (After Kamata, Tanabashi, and Kobayashi, Ref. 49.)

# Time Resolved Emission TRE



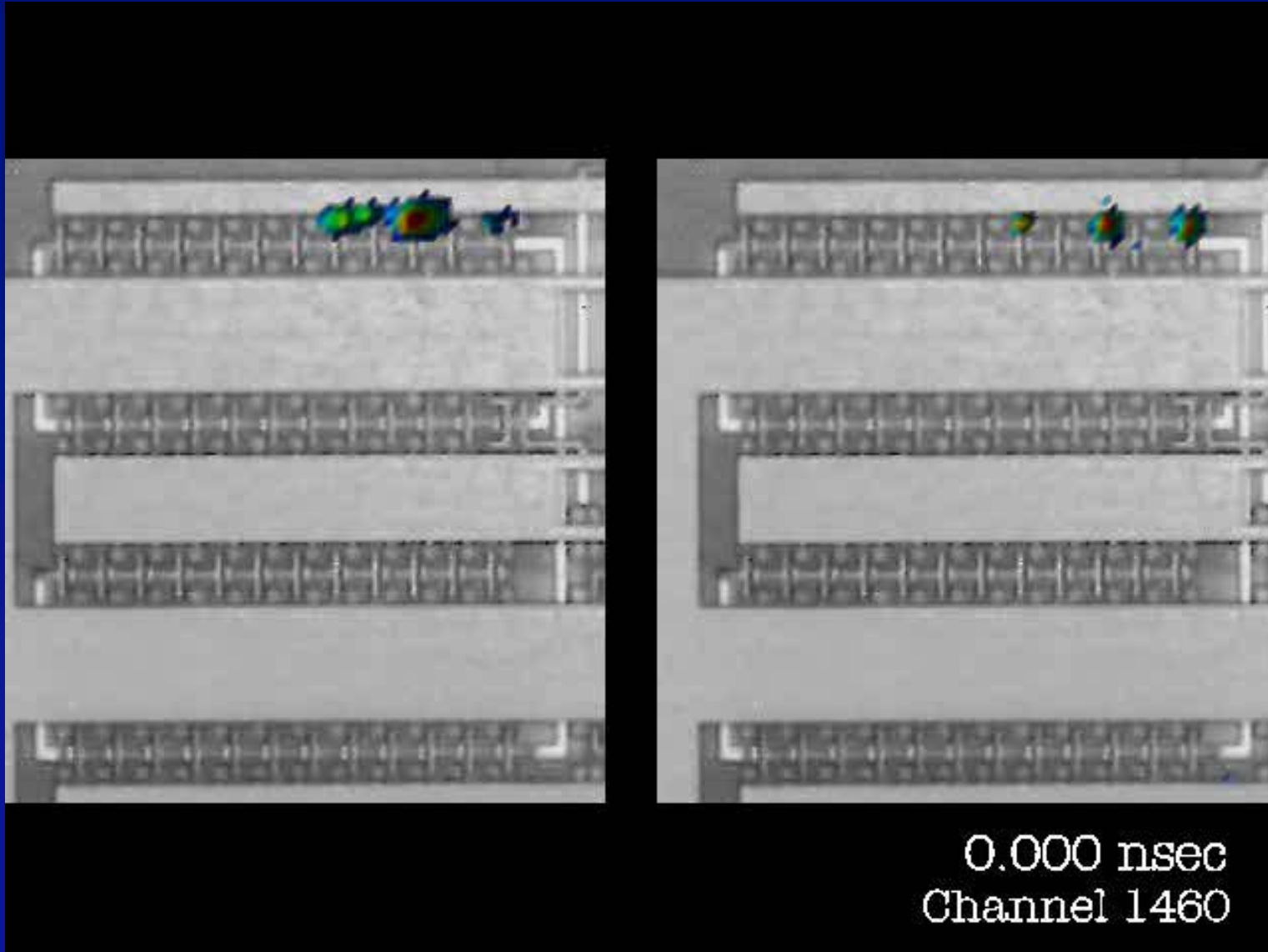
ref  
J.C.  
Tsng  
IBM

# Example: Propagation Delay



Ref: Credence

# TRE in Ring Oscillator - Demonstrator

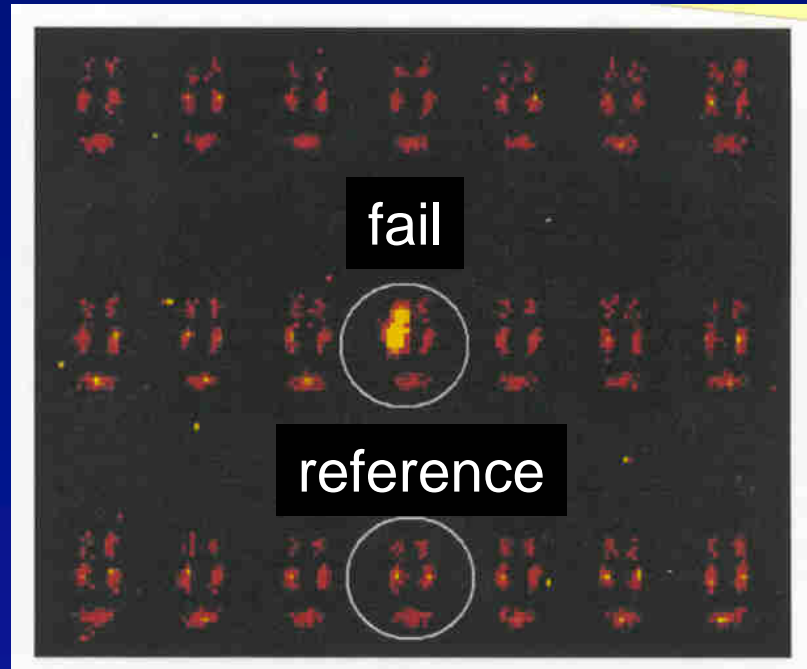


Courtesy IBM / Richard Ross

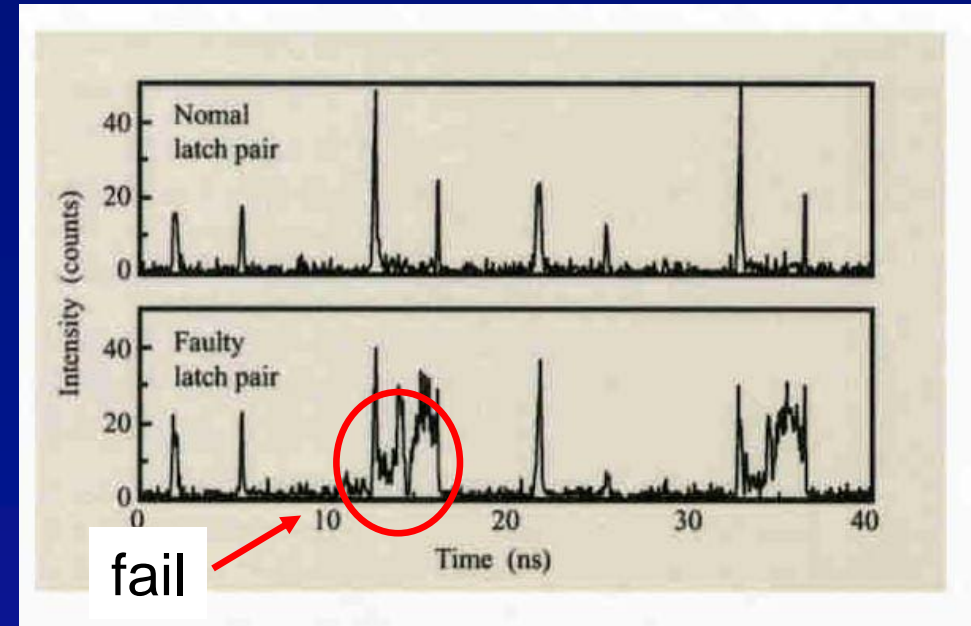


# Static Photoemission of Dynamic Signal

example design analysis:



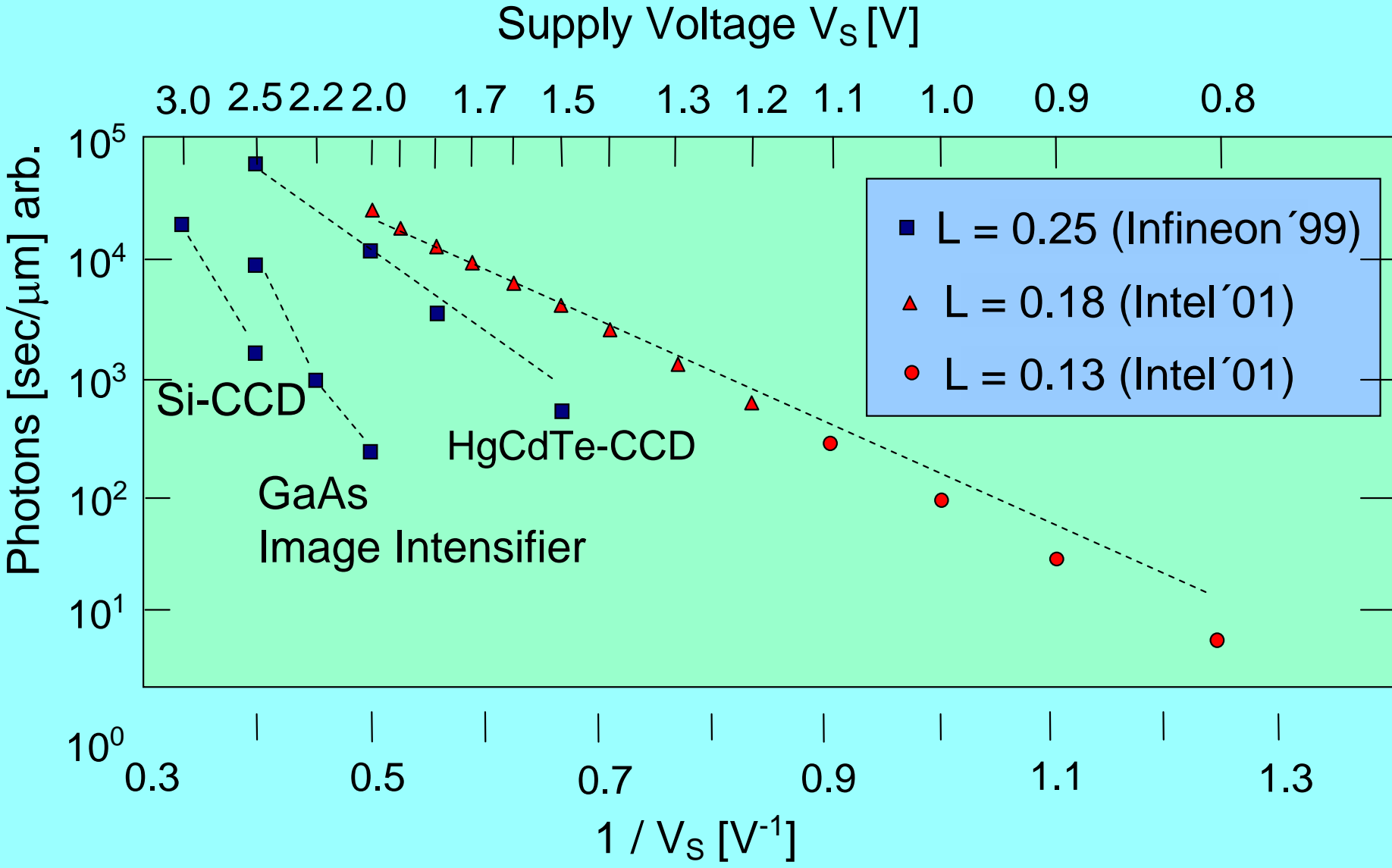
Time integrated image of light from a register file while running a test pattern producing a fail



,optical waveform' from normal and faulty latch pair

Ref J.C. Tsng, IBM

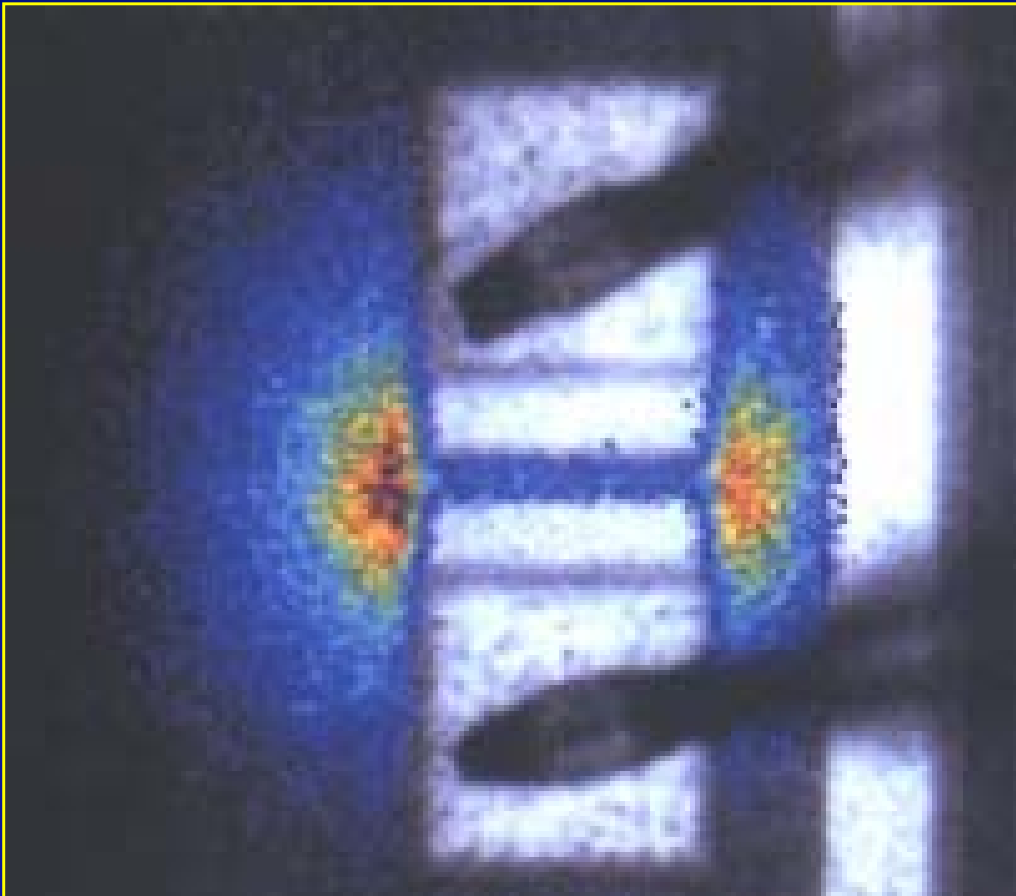
# Static emission



# Bipolar Diode

**Forward Bias**

**100 $\mu$ A**



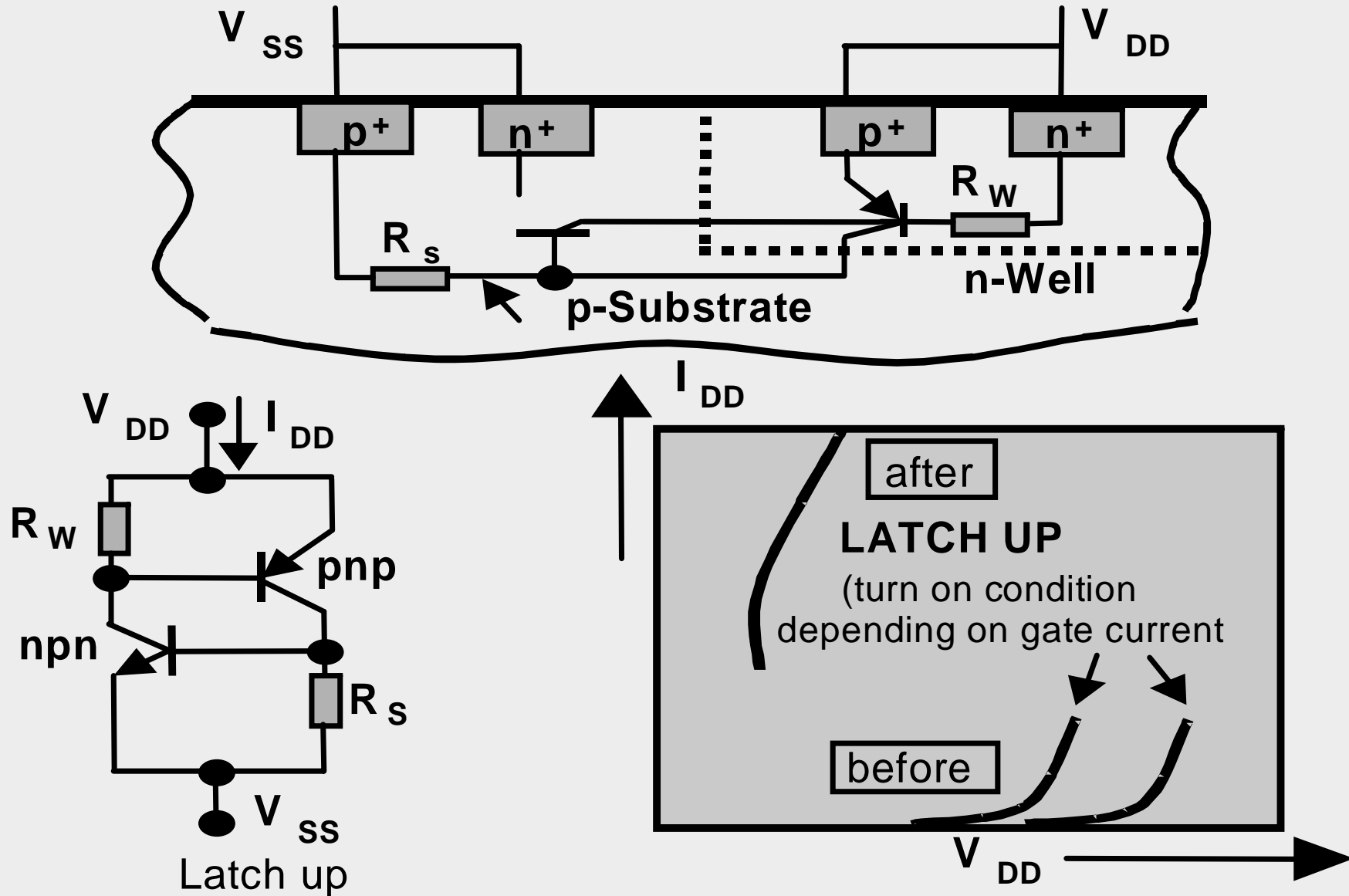
**Reverse Bias 10  $\mu$ A**

**Sensitivity limit: 10nA**



# PE-Classification of Emission Sources

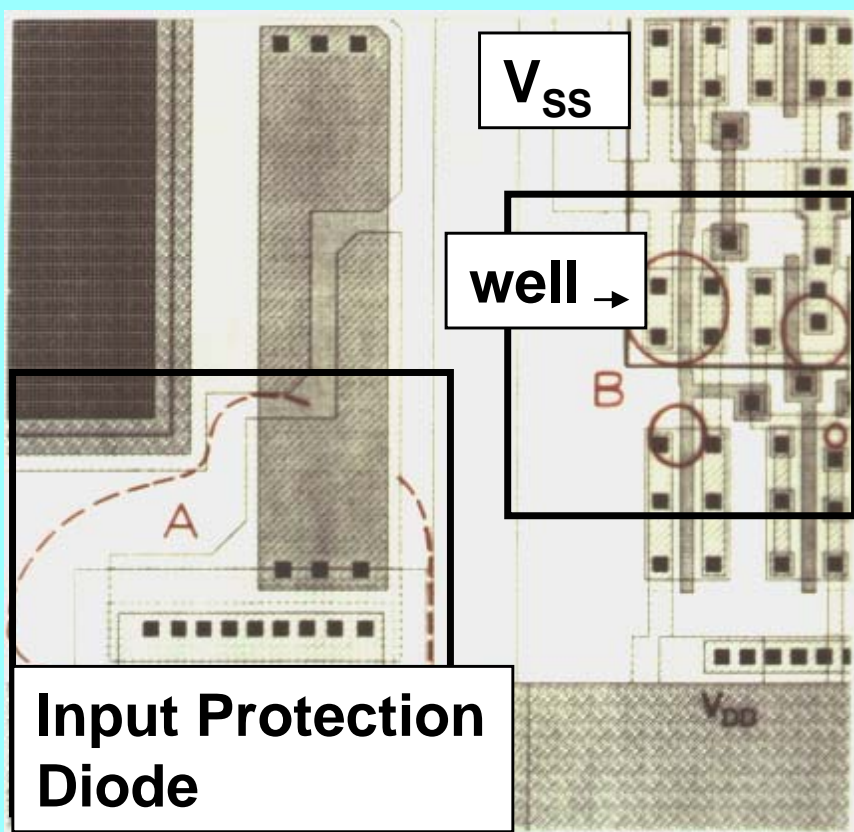
## Latch up



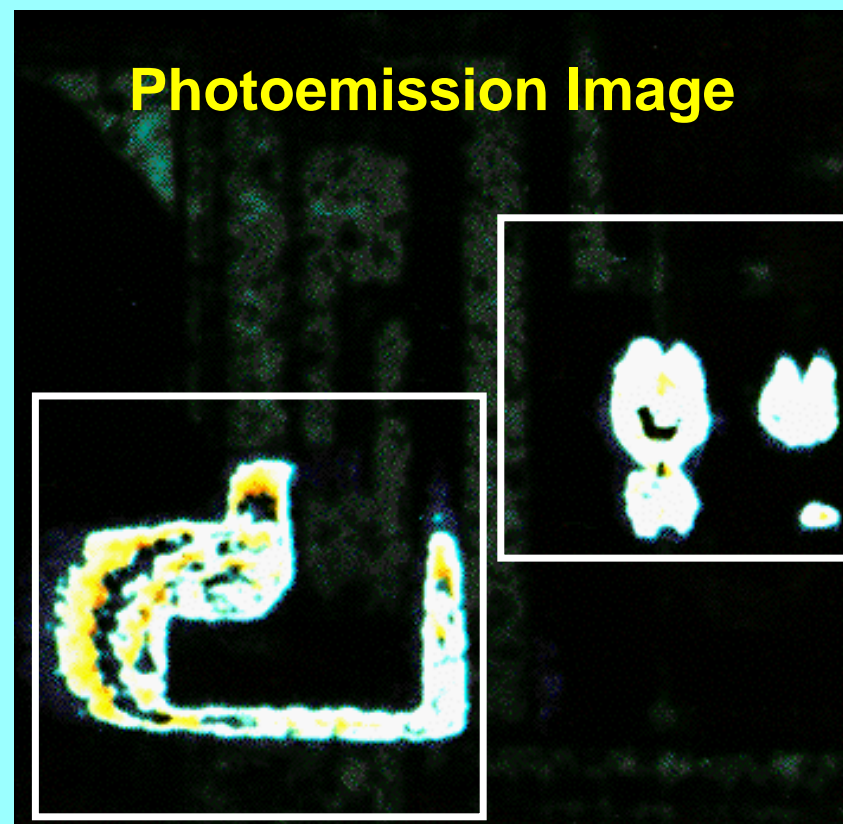
# PE-Classification of Emission Sources

## CMOS Latch-up

Latch-up operation: A: input protection diode  
B: latch-up area



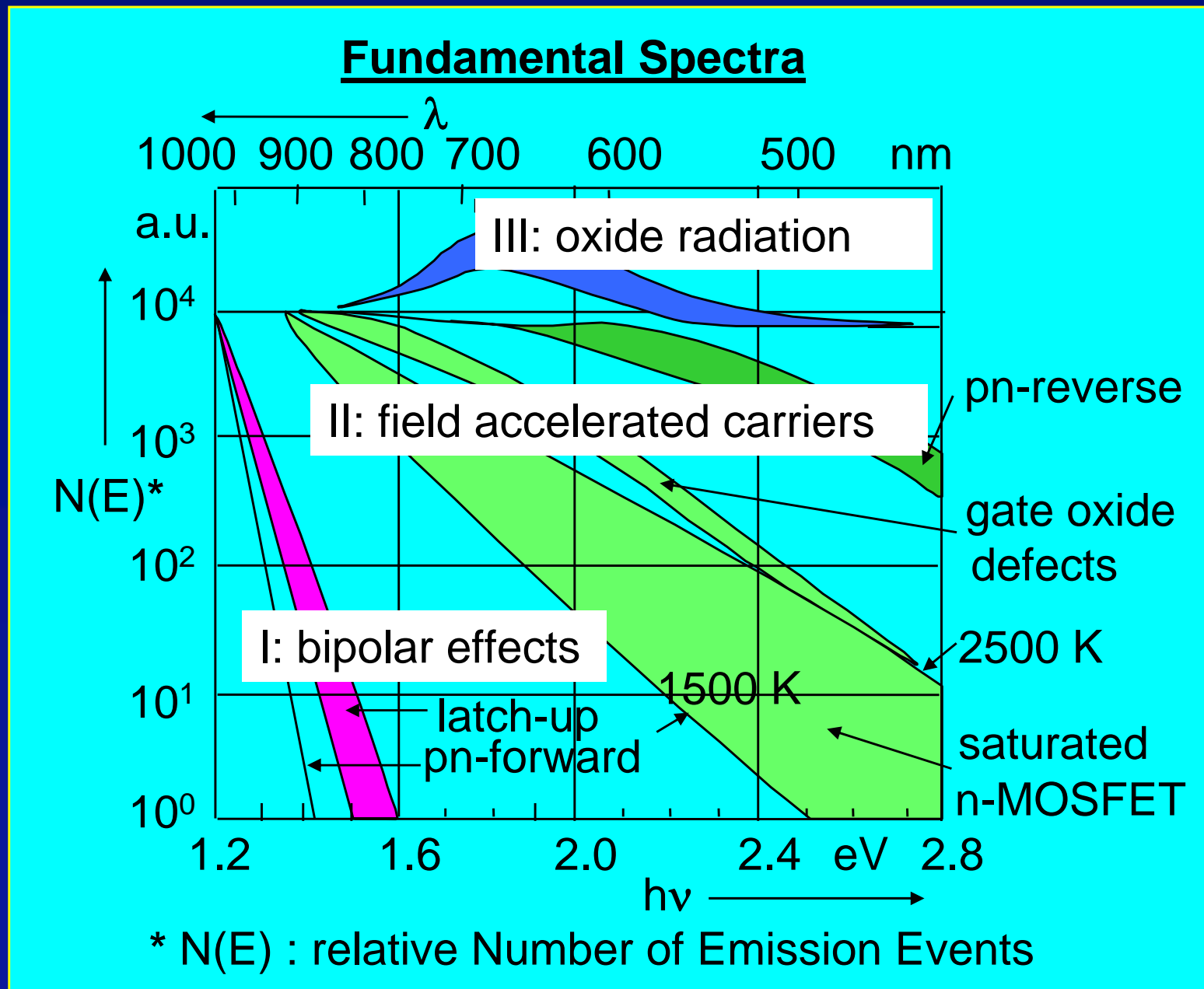
Layout



Superimposed emission

↔  
20 $\mu$ m

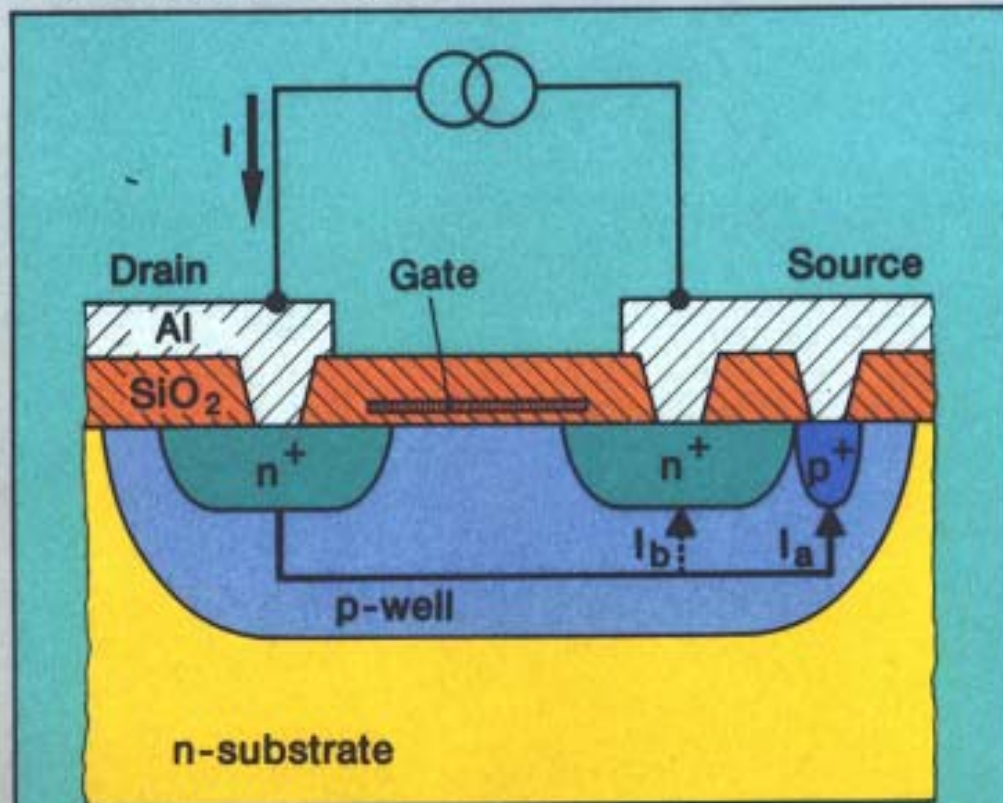
# PE-Classification of Emission Sources





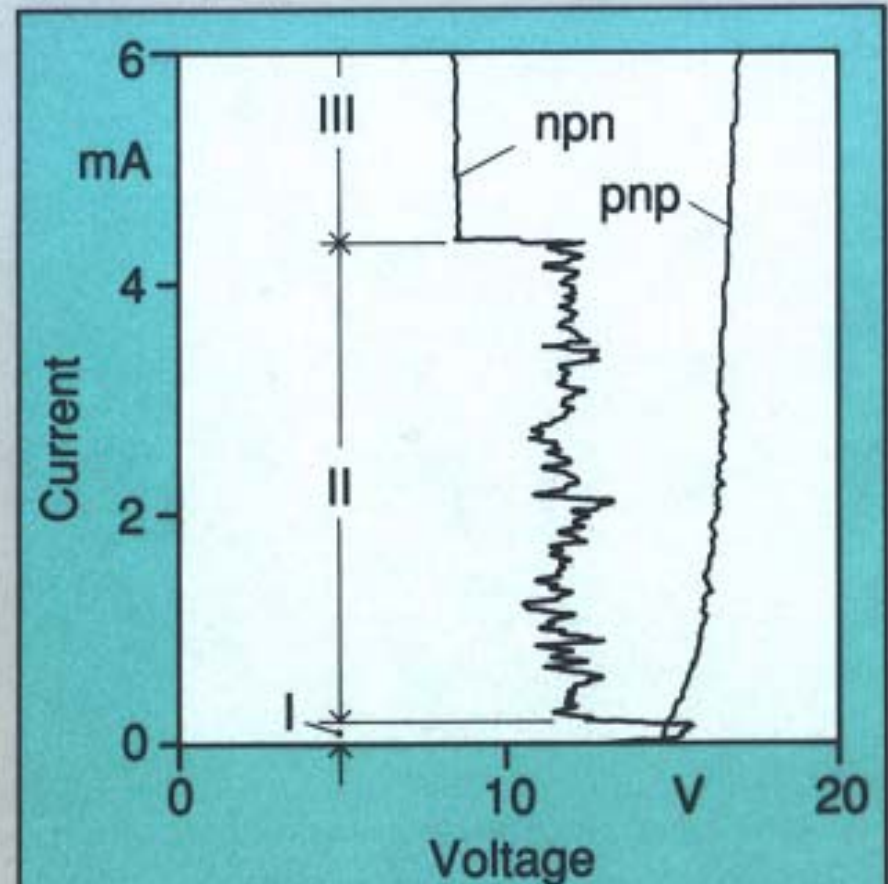
# ESD-protection structures: Characterization of different operation conditions

Cross-section A – B of the  
 n-channel type (npn)



- I: total current
- $I_a$ : leakage current of the reverse biased pn-junction
- $I_b$ : source injection current

V,I characteristic of the  
 npn and pnp devices

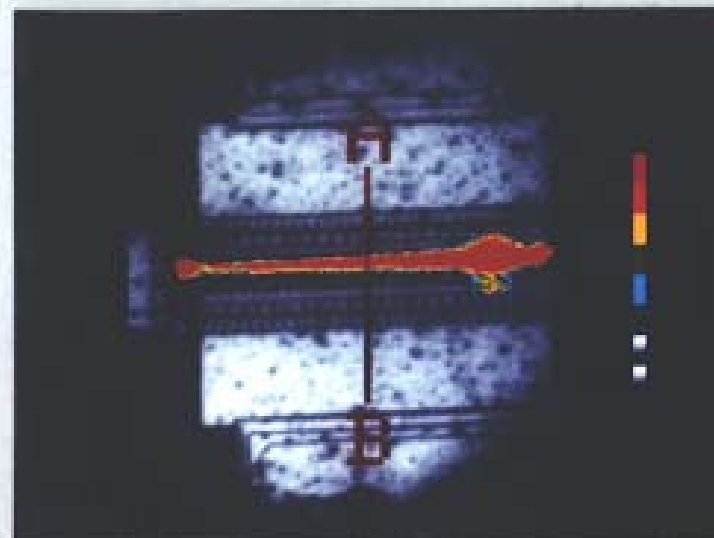


- I: low reverse currents (avalanche)
- II: snapback operation
- III: snapback steady state

# ESD-protection structures: Characterization of different operation conditions



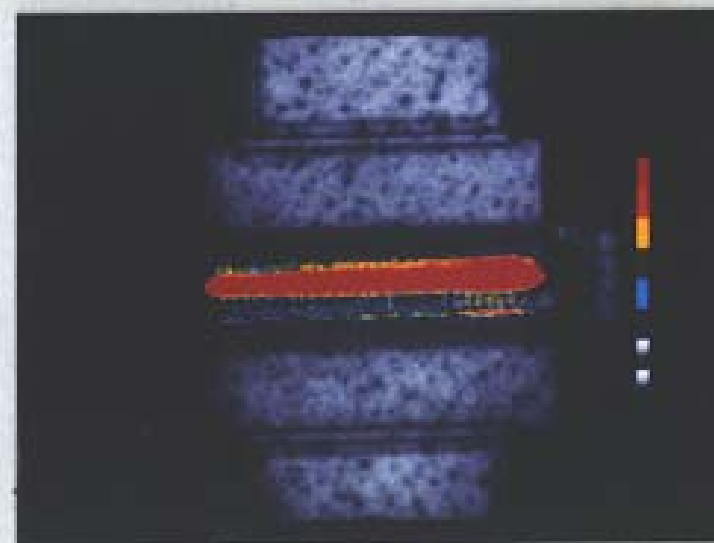
a



b

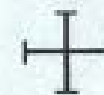


c



d

50  $\mu\text{m}$

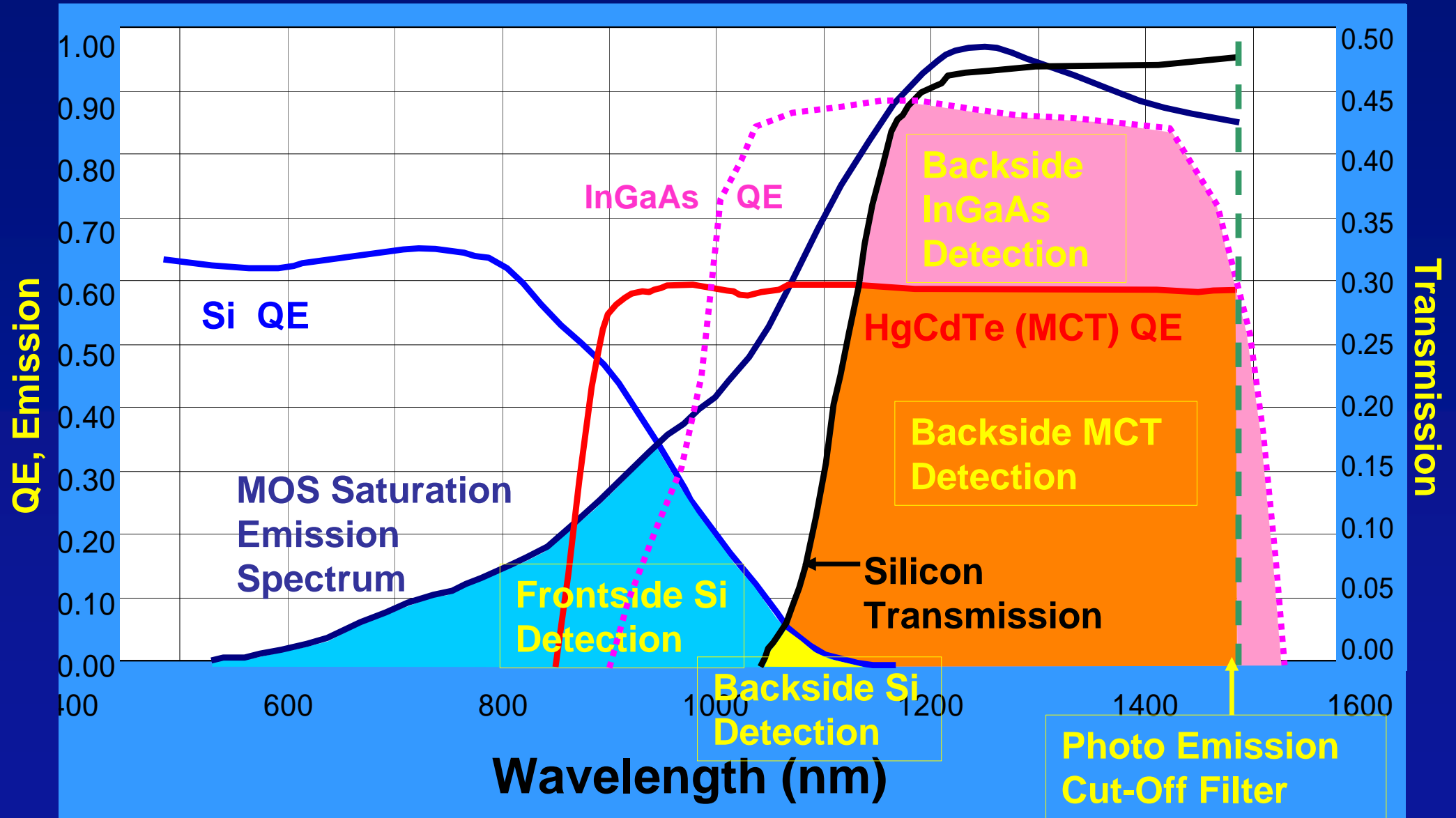


npn-structure: a) domain I ( $50 \mu\text{A}$ ), b) domain II (2mA), c) domain III (5 mA)  
pnp-structure: d) same emission characteristic for all currents (here: 2 mA)



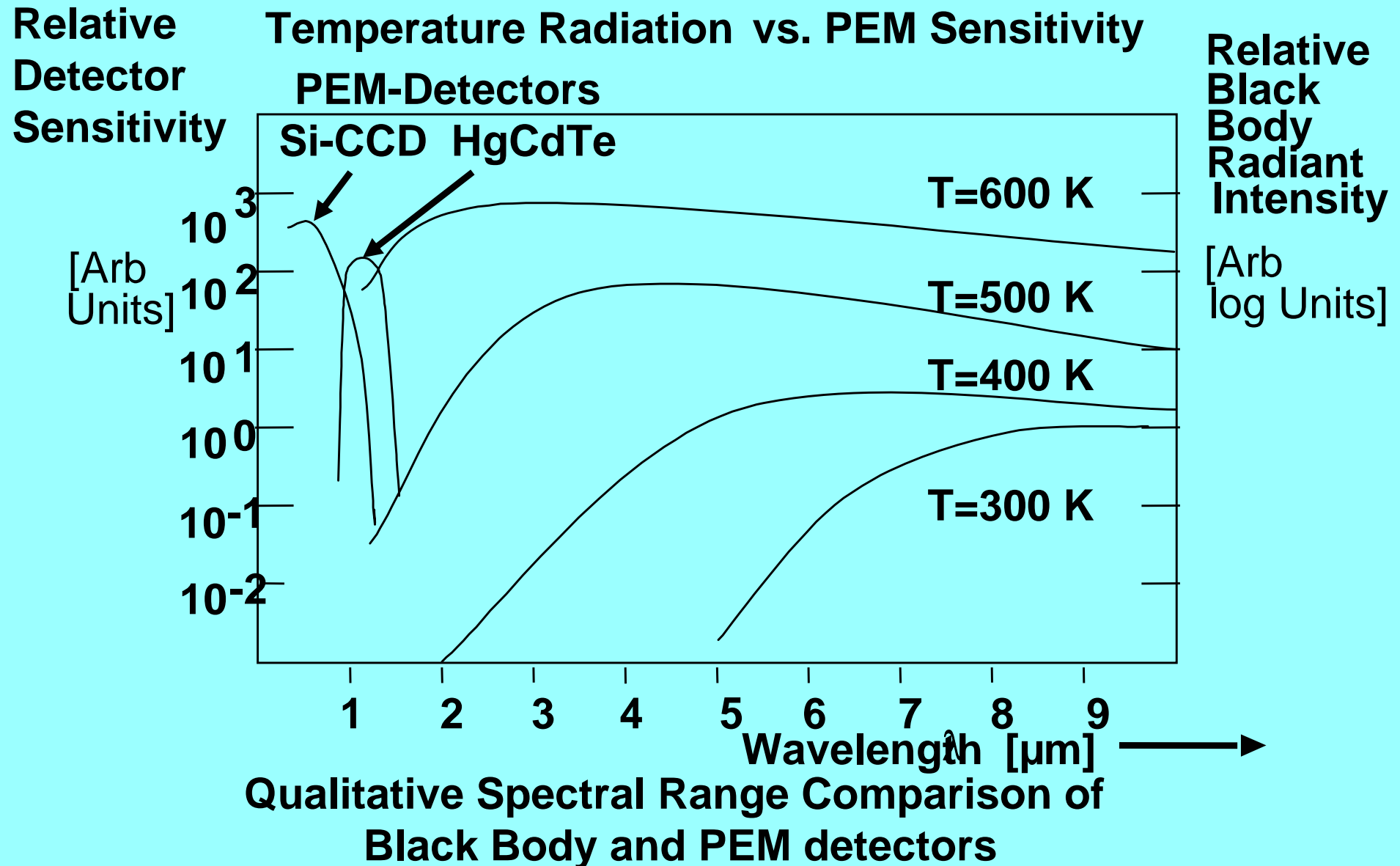
# Photon Emission Detection Evolution

Si CCD vs HgCdTe (MCT) vs InGaAs



Ref: Credence

# PEM-Equipment and Application



# Conclusion

**Photon Emission is the most powerful technique for localization of electrical function and failures in semiconductor devices, frontside and backside**